



Electrochemical Technology for New Materials Synthesis and Reprocessing

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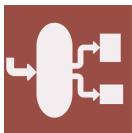
Message from the Guest Editor

Dear Colleagues,

The development of new technologies, materials, and electrochemical devices requires a deep understanding of the thermodynamics and kinetics of processes at the electrode boundary. Therefore, the Special Issue of «Electrochemical Technology for New Materials Synthesis and Reprocessing» is devoted to the following topics:

- Modeling of properties and structures of molten media and electrochemical devices;
- Kinetics and thermodynamics of electrode processes on solid and molten electrodes in molten salts;
- Materials for the aerospace industry and nuclear energy;
- New electrochemical and pyrochemical technologies;
- Production of metals and alloys by electrolysis of fluoride, chloride, and oxide melts;
- Promising functional materials for new-generation solid-oxide electrochemical devices.





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Message from the Editor-in-Chief

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